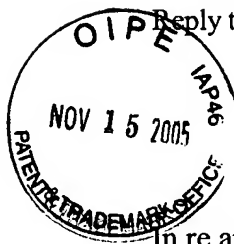


*ZPW*

U.S. Patent Application No. 10/791,014  
Reply to Office Action of August 17, 2005

Attorney Docket No. TSMC2000-488 / 24061.596  
Customer No. 42717



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of:

Chung-Shi Liu et al.

Serial No.: 10/791,014

Filed: March 2, 2004

For: PREVENTION OF POST CMP  
DEFECTS IN CU/FSG PROCESS

§  
§  
§  
§  
§  
§  
§  
§  
§

Group Art Unit: 2826

Examiner: Fetsum Abraham

Commissioner for Patents  
Mail Stop Amendment  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT**

Sir:

In response to the Office action of August 17, 2005, please amend the above-identified application as follows:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 3 of this paper.

**Remarks** begin on page 8 of this paper.